| L Number | Hits | Search Text | DB | Time stamp |
|---|---|---|---|---|
| 4 | 2512 | ((atomic adj layer adj (epitaxy deposition) ald (sequential digital) adj (CVD chemical adj vapor adj deposition))) | USPAT; US-PGPUB | 2003/09/21 20:17 |
| 6 | 12 | ((((atomic adj layer adj (epitaxy deposition) ald (sequential digital) adj (CVD chemical adj vapor adj deposition))) ) and nanolaminate) and silicide | USPAT; US-PGPUB | 2003/09/21 20:17 |
| 5 | 38 | (((atomic adj layer adj (epitaxy deposition) ald (sequential digital) adj (CVD chemical adj vapor adj deposition))) ) and nanolaminate | USPAT; US-PGPUB | 2003/09/21 20:42 |
| 7 | 1 | nanolaminate with silicide | USPAT; US-PGPUB | 2003/09/21 20:39 |
| 8 | 1 | ("6287635").PN. | USPAT; US-PGPUB | 2003/09/21 20:36 |
| 9 | 0 | nanolaminate with WSi$ | USPAT; US-PGPUB | 2003/09/21 20:40 |
| 10 | 1 | nanolaminate same (WSi$ silicide) | USPAT; US-PGPUB | 2003/09/21 20:37 |
| 11 | 1 | 09/954705.app. | USPAT; US-PGPUB | 2003/09/21 20:39 |
| 12 | 65 | nanolaminate | USPAT; US-PGPUB | 2003/09/21 20:40 |
| - | 3606 | (427/250-253,255.18,255.17,255.23,255.26,255 | USPAT; US-PGPUB | 2003/09/20 17:43 |
| - | 146 | ((427/250-253,255.18,255.17,255.23,255.26,255 and tungsten with silicide | USPAT; US-PGPUB | 2003/09/20 17:43 |
| - | 3 | (((427/250-253,255.18,255.17,255.23,255.26,255 and tungsten with silicide) and (atomic | USPAT; US-PGPUB | 2003/09/20 17:43 |
| - | 4 | ((427/250-253,255.18,255.17,255.23,255.26,255 and tungsten with silicide) and (atomic | USPAT; US-PGPUB | 2003/09/20 17:43 |
| - | 4867 | (427/250-253,255.18,255.17,255.23,255.26,255 | USPAT; US-PGPUB | 2003/09/20 17:43 |
| - | 57 | ((427/248.1,250-253,255.18,255.17,255.23,255 and (atomic adj layer adj deposition or | USPAT; US-PGPUB | 2003/09/20 17:43 |
| - | 5 | ((427/248.1,250-253,255.18,255.17,255.23,255 and (atomic adj layer adj deposition or | USPAT; US-PGPUB | 2003/09/20 17:43 |
| - | 0 | tungsten with silicide | USPAT; US-PGPUB | 2003/09/20 17:14 |
| - | 1705 | atomic adj layer adj deposition or ALD | USPAT; US-PGPUB | 2003/09/20 17:17 |
| - | 90 | (atomic adj layer adj deposition or ALD) and tungsten with silicide | USPAT; US-PGPUB | 2003/09/20 17:35 |
| - | 89 | (atomic adj layer adj deposition or ALD) and WSi$7 | USPAT; US-PGPUB | 2003/09/20 18:02 |
| - | 58 | ((atomic adj layer adj deposition or ALD) and WSi$7) not ((atomic adj layer adj deposition or ALD) and tungsten with silicide) | USPAT; US-PGPUB | 2003/09/20 17:36 |
| - | 0 | (((atomic adj layer adj deposition or ALD) and WSi$7) not ((atomic adj layer adj deposition or ALD) and tungsten with silicide)) and @ad<=2001020 | USPAT; US-PGPUB | 2003/09/20 17:36 |
| - | 14 | (((atomic adj layer adj deposition or ALD) and WSi$7) not ((atomic adj layer adj deposition or ALD) and tungsten with silicide)) and @ad<=20001020 | USPAT; US-PGPUB | 2003/09/20 19:15 |
| - | 71 | (427/255.392).CCLS. | USPAT; US-PGPUB | 2003/09/20 17:43 |
| - | 5 | ((427/255.392).CCLS.) and (atomic adj layer adj deposition ald (sequential digital) adj (CVD chemical adj vapor adj deposition)) | USPAT; US-PGPUB | 2003/09/20 19:12 |
| - | 2 | ((427/255.392).CCLS.) and (atomic adj layer adj epitaxy ale) | USPAT; US-PGPUB | 2003/09/20 18:01 |
| - | 58 | ((427/248.1,250-253,255.18,255.17,255.23,255 and (atomic adj layer adj epitaxy or ALE) | USPAT; US-PGPUB | 2003/09/20 17:43 |
| - | 0 | (((427/248.1,250-253,255.18,255.17,255.23,255 and (atomic adj layer adj epitaxy or ALE)) and WSi$7 | USPAT; US-PGPUB | 2003/09/20 17:43 |

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|---|---|---|---|---|
| - | 1 | (((427/248.1,250-253,255.18,255.17,255.23,255.27,255.393). and (atomic adj layer adj epitaxy or ALE)) | USPAT; US-PGPUB | 2003/09/20 19:20 |
| - | 2512 | (atomic adj layer adj (epitaxy deposition) ald (sequential digital) adj (CVD chemical adj vapor adj deposition)) | USPAT; US-PGPUB | 2003/09/20 20:11 |
| - | 0 | ((atomic adj layer adj (epitaxy deposition) ald (sequential digital) adj (CVD chemical adj vapor adj deposition))) and hydrate with substrate | USPAT; US-PGPUB | 2003/09/21 20:16 |
| - | 1 | ((atomic adj layer adj (epitaxy deposition) ald (sequential digital) adj (CVD chemical adj vapor adj deposition))) and hydrated with substrate | USPAT; US-PGPUB | 2003/09/20 19:15 |
| - | 130 | ((atomic adj layer adj (epitaxy deposition) ald (sequential digital) adj (CVD chemical adj vapor adj deposition))) and atomic with hydrogen | USPAT; US-PGPUB | 2003/09/20 20:50 |
| - | 22 | ((((atomic adj layer adj (epitaxy deposition) ald (sequential digital) adj (CVD chemical adj vapor adj deposition))) and atomic with hydrogen) and @ad<=20001020) and (silicide tungsten titanium) | USPAT; US-PGPUB | 2003/09/20 19:43 |
| - | 65 | ((atomic adj layer adj (epitaxy deposition) ald (sequential digital) adj (CVD chemical adj vapor adj deposition))) and atomic adj hydrogen | USPAT; US-PGPUB | 2003/09/20 19:42 |
| - | 49 | (((atomic adj layer adj (epitaxy deposition) ald (sequential digital) adj (CVD chemical adj vapor adj deposition))) and atomic adj hydrogen) and (silicide tungsten titanium) | USPAT; US-PGPUB | 2003/09/20 19:43 |
| - | 14 | ((((atomic adj layer adj (epitaxy deposition) ald (sequential digital) adj (CVD chemical adj vapor adj deposition))) and atomic adj hydrogen) and (silicide tungsten titanium)) and @ad<=20001020 | USPAT; US-PGPUB | 2003/09/20 19:50 |
| - | 1209 | hydrogen with reduce with (chlorine chloride halogen halide) | USPAT; US-PGPUB | 2003/09/20 19:50 |
| - | 3 | (hydrogen with reduce with (chlorine chloride halogen halide)) and (atomic adj layer adj (epitaxy deposition) ald (sequential digital) adj (CVD chemical adj vapor adj deposition)) | USPAT; US-PGPUB | 2003/09/20 20:00 |
| - | 100 | hydrogen with scavenge with chlori?e | USPAT; US-PGPUB | 2003/09/20 20:01 |
| - | 85 | (hydrogen with scavenge with chlori?e) and @ad<=20001020 | USPAT; US-PGPUB | 2003/09/20 20:01 |
| - | 3 | ((hydrogen with scavenge with chlori?e) and @ad<=20001020) and silicide | USPAT; US-PGPUB | 2003/09/20 20:03 |
| - | 4 | ((hydrogen with scavenge with chlori?e) and @ad<=20001020) and tungsten | USPAT; US-PGPUB | 2003/09/20 20:04 |
| - | 2 | ((hydrogen with scavenge with chlori?e) and @ad<=20001020) and (CVD ALD atomic adj layer adj (deposition epitaxy) chemical adj vapor adj deposition) | USPAT; US-PGPUB | 2003/09/20 20:05 |
| - | 48 | ((atomic adj layer adj (epitaxy deposition) ald (sequential digital) adj (CVD chemical adj vapor adj deposition))) and tungsten adj layer | USPAT; US-PGPUB | 2003/09/20 20:12 |
| - | 25 | (((atomic adj layer adj (epitaxy deposition) ald (sequential digital) adj (CVD chemical adj vapor adj deposition))) and tungsten adj layer) and hydrogen | USPAT; US-PGPUB | 2003/09/20 20:12 |
| - | 45 | (((atomic adj layer adj (epitaxy deposition) ald (sequential digital) adj (CVD chemical adj vapor adj deposition))) and atomic with hydrogen) and @ad<=20001020 | USPAT; US-PGPUB | 2003/09/20 20:50 |

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|---|---|---|---|---|
| - | 65 | ((atomic adj layer adj (epitaxy deposition) ald (sequential digital) adj (CVD chemical adj vapor adj deposition))) and atomic adj hydrogen | USPAT; US-PGPUB | 2003/09/20 20:50 |